

Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No.	NOVLP094/NVLS-2919
	Application No.:	10/789,103
	Applicant	Wu et al.
	Filing Date	February 27, 2004
	Group	1762
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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
/BC/	1.	2003/0224156	12.2003	Kirner et al.			
	2.	2003/0111263	06.2003	Fornof et al.			
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	6.	7,098,149	08.2006	Lukas et al.			
	7.	2006/0040507	02.2006	Mak et al.			
	8.	2005/0230834	10.2005	Schmitt et al.			
	9.	2006/0105566	05.2006	Waldfried et al.			
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	15.	6,572,925 B2	06.2003	Zubkov et al.			
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	17.	6,413,583 B1	07.2002	Moghadam et al.			
	18.	6,407,013 B1	06.2002	Li et al.			
/BC/	19.	6,365,528 B1	04.2002	Sukharev et al.			

Foreign Patent or Published Foreign Patent Application

Examiner Initial		Document No.	Publication Date	Country or Patent Office	Class	Sub-Class	Translation	
							Yes	No
/BC/	20.	WO 03/052794 A2	26.06.2003	PCT				
/BC/	21.	WO 03/005429 A1	16.01.2003	PCT				

Other Documents

Examiner Initial	No.	Author, Title, Place (e.g. Journal) of Publication, Date
/BC/	22.	U.S. Office Action mailed November 30, 2006, from U.S Application No. 10/927,777 [Atty Dkt No. NOVLP106/NVLS-2930].

Examiner	/Bret Chen/	Date Considered	02/04/2008
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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/BC/	23.	U.S. Office Action mailed March 28, 2007, from U.S Application No. 10/820,525 [Atty Dkt No. NOVLP091/NVLS-2889].
	24.	U.S. Notice of Allowance and Fee Due mailed December 19, 2006, from U.S. Application No. 10/800,409. [NOVLP098/NVLS-2907]
	25.	U.S. Office Action mailed April 9, 2007, from U.S Application No. 10/800,409 [Atty Dkt No. NOVLP098/NVLS-2907].
	26.	Niu et al., "Methods for Improving the Cracking Resistance of Low-K Dielectric Materials," Novellus Systems, Inc., Appl. No. 11/376,510, filed March 14,2006, pages 1-28. [NOVLP099D1/NVLS-2896D1]
	27.	U.S. Office Action dated May 22, 2007, from U.S. Application No. 11/376,510 [Atty Dkt: NOVLP099D1/NVLS-2896D1]
	28.	U.S. Notice of Allowance and Fee Due mailed April 9, 2007, from U.S. Application No. 10/927,777. [NOVLP106/NVLS-2930]
	29.	Allowed Claims from U.S. Application No. 10/927,777. [NOVLP106/NVLS-2930]
	30.	U.S. Final Office Action mailed April 3, 2007, from U.S Application No. 10/941,502 [Atty Dkt No. NOVLP107/NVLS-2932].
	31.	U.S. Notice of Allowance and Fee Due mailed December 20, 2005, from U.S. Application No. 10/860,340. [NOVLP099/NVLS-2896]
	32.	Wu et al., "PECVD Methods for Producing Ultra Low-K Dielectric Films Using UV Treatment," Novellus Systems, Inc., Appl. No.11/608,056, filed December 7, 2006, pages 1-34. [NOVLP196/NVLS-3238]
	33.	Wu et al., "Methods for Improving Performance of ODC Films with Dielectric Constant < 4.0," Novellus Systems, Inc., Appl. No. 11/693,661, filed March 29, 2007, pages 1-46. [NOVLP200/NVLS-3269]
	34.	Allowed Claims from U.S. Application No. 10/860,340. [NOVLP099/NVLS-2896]
	35.	U.S. Notice of Allowance and Fee Due mailed September 19, 2007, from U.S. Application No. 10/800,409. [NOVLP098/NVLS-2907]
	36.	Allowed Claims from U.S. Application No. 10/800,409. [NOVLP098/NVLS-2907]
	37.	U.S. Office Action mailed October 4, 2007, from U.S Application No. 10/820,525 [Atty Dkt No. NOVLP091/NVLS-2889].
/BC/	38.	U.S. Office Action mailed October 29, 2007, from U.S Application No. 11/764,750 [Atty Dkt No. NOVLP106D1].

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